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KIM et al.(10) **Pub. No.: US 2023/0400266 A1**(43) **Pub. Date: Dec. 14, 2023**(54) **APPARATUS FOR HIGH TEMPERATURE GAS, INCLUDING THREE-DIMENSIONAL LATTICE STRUCTURE, AND METHOD FOR MANUFACTURING SAME**(30) **Foreign Application Priority Data**

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ABSTRACT

Disclosed is a device for high-temperature gas including one or more partitions and three-dimensional lattice structures of different shapes, wherein different spaces formed by the partitions include the three-dimensional lattice structures of different shapes.

